

Case Docket No. ASMINT.055AUS

Date: November 3, 2003

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s)

Timmermans et al.

Appl. No.

10/690,215

Filed

October 20, 2003

∝ For

METHOD FOR THE

DEPOSITION OF A

REACTION CHAMBER FOR

THE DEPOSITION OF SILICON NITRIDE FILMS

Examiner

Unknown

Group Art Unit:

Unknown

I hereby certify that this correspondence and all marked attachments are being deposited with the United States Postal Service as first class mail in an envelope addressed to: Commissioner for Patents, P.O. Box 1450, Alexandria, VA 22313-1450, on

November 3, 2003 (Date)

of Children

Adeel S. Akhtar, Reg. No. 41 394

TRANSMITTAL LETTER

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Enclosed for filing in the above-identified application are:

- (X) An Information Disclosure Statement.
- (X) A PTO Form 1449 with fifty-seven (57) references.
- (X) Eight (8) references enclosed.
- (X) The Commissioner is hereby authorized to charge any additional fees which may be required, or credit any overpayment, to Account No. 11-1410.
- (X) Return prepaid postcard.

Adeel S. Akhta

Registration No. 41,394

Attorney of Record Customer No. 20,995

(415) 954-4114



INFORMATION DISCLOSURE STATEMENT

Flicant : Timmermans et al.

App. No. : 10/690,215

Filed : October 20, 2003

For : METHOD FOR THE DEPOSITION OF A

REACTION CHAMBER FOR THE DEPOSITION OF SILICON NITRIDE

FILMS

Examiner : Unknown

Group Art Unit : Unknown

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Dear Sir:

Enclosed is form PTO-1449 listing 57 references. Copies of disclosed U.S. patents and/or publications are not included pursuant to PTO waiver of the requirement under 37 C.F.R. § 1.98(a)(2)(i) for applications filed after June 30, 2003. Copies of all other references are enclosed.

This Information Disclosure Statement is being filed with an RCE or within three months of the filing date of this application and no fee is required in accordance with 37 C.F.R. § 1.97(b)(1), (b)(2), or (b)(4).

Respectfully submitted,

KNOBBE, MARTENS, OLSON & BEAR, LLP

Dated: October 31, 2003

By: Adeel S. Akhtar

Registration No. 41,394

Attorney of Record

Customer No. 20,995

(415) 954-4114

FORM	

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE ATTY. DOCKET NO. ASMINT.055AUS

APPLICATION NO. **10/690,215

NOV 1 0 2007 USE SEVERAL SHEETS IF NECESSARY)

EINFORMATION DISCLOSURE STATEMENT BY APPLICANT

APPLICANT Timmermans et al.

FILING DATE October 20, 2003 **GROUP** Unknown

				U.S. PATENT DOCUMENTS		·	
EXAMINER INITIAL		DOCUMENT NUMBER	DATE	NAME	CLASS	SUBCLASS	FILING DATE (IF APPROPRIATE)
	1	3,011,006	11/28/61	Nicholson et al.			
	2	3,874,919	4/1/75	Lehman		_	
	3	4,374,158	2/15/83	Taniguchi et al.			
	4	4,377,347	3/22/83	Hanmyo et al.			
	5	4,389,967	6/28/83	Shimoda et al.			
	6	4,428,975	1/31/84	Dahm et al.			
	7	4,499,354	2/12/85	Hill et al.			
	8	4,522,849	6/11/85	Lewandowski			
	9	4,592,307	6/3/86	Jolly			
	10	4,633,051	12/30/86	Olson			
	11	4,653,428	3/31/87	Wilson et al.			
	12	4,692,556	9/8/87	Bollen et al.			
	13	4,976,996	12/11/90	Monkowski et al.			
	14	4,978,567	12/18/90	Miller			
	15	4,984,904	1/15/91	Nakano et al.			
	16	5,027,746	7/2/91	Frijlink			
	17	5,065,698	11/19/91	Koike			
	18	5,104,514	4/14/92	Quartarone			
	19	5,128,958	7/14/92	Nagashima et al.			
	20	5,246,500	9/21/93	Samata et al.			
	21	5,271,967	12/21/93	Kramer et al.		İ	
	22	5,315,092	5/24/94	Takahashi et al.			
	23	5,336,327	8/9/94	Lee			
	24	5,360,269	11/1/94	Ogawa et al.			
	25	5,421,893	6/6/95	Perlov			
	26	5,456,761	10/10/95	Auger et al.			
	27	5,474,618	12/12/95	Allaire			

EXAMINER

DATE CONSIDERED

*EXAMINER: INITIAL IF CITATION CONSIDERED, WHETHER OR NOT CITATION IS IN CONFORMANCE WITH MPEP 609; DRAW LINE THROUGH CITATION IF NOT IN CONFORMANCE AND NOT CONSIDERED, INCLUDE COPY OF THIS FORM WITH NEXT COMMUNICATION TO APPLICANT.

FORM PTO-1449

U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE

ATTY. DOCKET NO. ASMINT.055AUS

APPLICATION NO. **10/690,215

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INFORMATION DISCLOSURE STATEMENT
BY APPLICANT

APPLICANT
Timmermans et al.

Timmermans et al.

October 20, 2003

FILING DATE

GROUP Unknown

(USE SEVERAL SHEETS IF NECESSARY)

U.S. PATENT DOCUMENTS EXAMINER DOCUMENT NUMBER SUBCLASS DATE NAME **CLASS** FILING DATE INITIAL (IF APPROPRIATE) 28 5,493,987 2/27/96 McDiarmid et al. 29 5,514,439 5/7/96 Sibley 30 5,562,774 10/8/96 Breidenbach et al. 31 5,571,333 11/5/96 Kanaya 32 5,594,482 1/14/97 Ohashi 33 3/17/98 5,728,629 Mizuno et al. 34 5,788,799 8/4/98 Steger et al. 35 8/25/98 5,798,016 Oehrlein et al. De Boer et al. 36 5,902,407 5/11/99 37 5,904,778 5/18/99 Lu et al. 38 Wu 5,910,221 6/8/99 39 6,056,823 5/2/00 Sajoto et al. 40 6,066,209 5/23/00 Sajoto et al. 41 6/6/00 6,071,573 Koemtzopoulos et al. 42 6,120,640 9/19/00 Shih et al: 43 10/10/00 6,129,808 Wicker et al. 44 6,170,429 B1 1/9/01 Schoepp et al. 45 6,214,425 4/10/01 Spinelli et al. 46 6,227,140 B1 5/8/01 Kennedy et al. 47 6,325,857 12/4/01 Miyoshi 48 6,325,858 B1 12/4/01 Wengert et al. 49 1/29/02 6,342,691 B1 Johnsgard et al.

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/	SPE "	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE	ATTY. DOCKET NO ASMINT.055AUS	APPLICATION NO. **10/690,215
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	FOREIGN PATENT DOCUMENTS							
EXAMINER		DOCUMENT NUMBER	DATE	COUNTRY	CLASS	SUBCLASS	TRANSLATION	
INITIAL							YES	NO
	50	WO 95/31582	11/23/95	PCT				
-	51	WO 97/06288	2/20/97	PCT				
	52	WO 99/23276	5/14/99	PCT		· · · · ·		
	53	EP 0 229 488	7/22/87	EPO				

EXAMINER INITIAL		OTHER DOCUMENTS (INCLUDING AUTHOR, TITLE, DATE, PERTINENT PAGES, ETC.)						
		Linke et al., "Behavior of Boron-Doped Graphites, Plasma-Sprayed B ₄ C ₁ and a-C/B:H as Plasma-Facing Materials," Fusion Technology, Vol. 20, (September 1991), pp. 227-230.						
	Moslehi et al., "Compositional Studies of Thermally Nitrided Silicon Dioxide (Nitroxide)," J. Electrochem Soc., Vol. 1. No. 9, pp. 2189-2197 (September 1985).							
	Murarka et al., "Thermal Nitridation of Silicon in Ammonia Gas: Composition and Oxidation Resistance of the Result Films," J. Electrochem. Soc., Vol. 126, No. 6, pp. 996-1003 (June 1979).							
		Ponnekanti et al., "Failure mechanisms of anodized aluminum parts used in chemical vapor deposition chambers," <i>J. Vac. Sci. Technol</i> , Vol. 14, No. 3, (May/June 1996), pp. 1127-1131.						

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EXAMINER DATE CONSIDERED